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研究論文

(a) 査読付の研究論文

1. S. Tamura, M. Iwaoka, **Y. Sato**, M. Kobayashi, M. Kakihana, and K. Tomita: "Investigation of the up-conversion properties of Er-Yb-doped calcium tantalates with various Ca/Ta ratios", J. Photopolym. Sci. Technol. 30 (2017) 507–512.
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3. 小向哲史, 横山潤, **佐藤泰史**, 加藤英樹, 垣花真人: "緑色蛍光体(Ba, Sr)₂SiO₄:Eu²⁺のフラックス還元焼成条件と発光特性の関係, 粉体および粉末冶金 **63** (2016) 855–860.
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(b) 総説、解説および著書

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(c) 査読なしのプロシーディングス

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